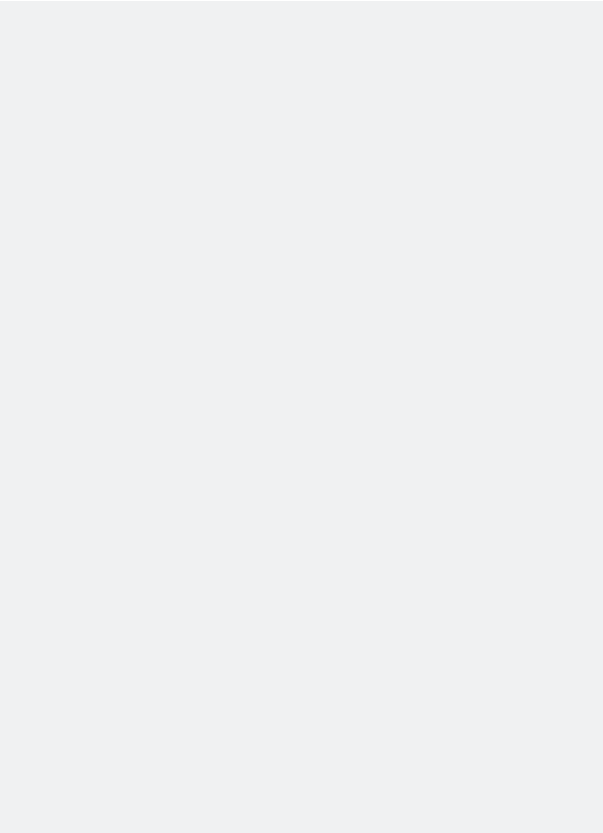


AFC® J02 (CLASS 100-1000/ISO5-6)



Introduction

AFC® J02 is a cleanroom fabric specifically developed for semiconductor photolithography areas. It utilizes invisible conductive yarn technology to help reduce visual fatigue, enhancing user comfort and concentration during long working hours. In addition, it offers excellent electrostatic dissipation, superior cleanliness, and high stain resistance, effectively preventing particles, fibers, and contaminants from entering the production environment and safeguarding precision manufacturing processes.

Characteristic

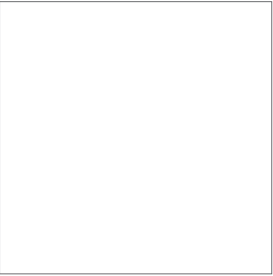
- (1) Relieves eye fatigue, improves focus and productivity.
- (2) Cleanroom-grade; ideal for photolithography environments.
- (3) High particle retention to block micro-particle intrusion.
- (4) Anti-static to prevent electrostatic interference.
- (5) Breathable and soft for long-wear comfort.

簡 介

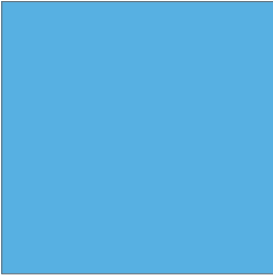
AFC®J02為半導體黃光區專用無塵布料，透過隱形導電絲技術，減緩視覺負擔，提升使用者的視覺舒適度與工作專注力。同時具有優越的靜電消除效果、無塵性能和高抗污能力，能有效防止微粒、纖維及污染物進入生產環境，保障產品的精密製程。

特 性

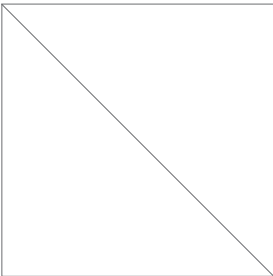
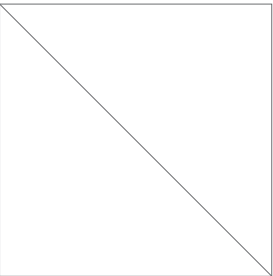
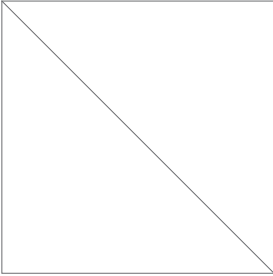
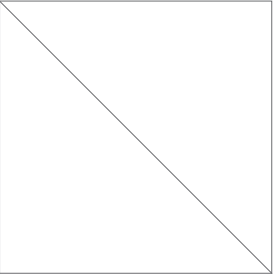
- (1) 減少操作人員視覺疲勞，提升生產效率。
- (2) 無塵等級符合國際標準，潔淨度極高，適用於黃光區及高潔淨環境。
- (3) 高顆粒阻隔力，有效防止微粒進入作業環境。
- (4) 良好的靜電消除效果，防止靜電干擾。
- (5) 優異透氣性與布料觸感，提升長時間穿著的舒適體驗。



White (BBKW86M)



Blue (BBK1T6X)



Specification

Style No.	AFC® J02	Test Method
Composition	98% Polyester Filament Yarn 2% Conductive Filament Yarn	
Weave	3/2 twill, 5 mm Grid	
Weight	178 g/y, 124 /m² ± 5%	
Width	60 inch 152cm ± 1"	
Density	Warp : 175 ends / inch 69 ends / cm Weft : 122 ends / inch 48 ends / cm	
Surface Resistivity	10 ⁹⁻¹¹ ohm/square	
Tensile Strength	Warp : ≥ 80 kgf Weft : ≥ 40 kgf	ASTM D5035
Tear Strength	Warp : ≥ 2.0 kgf Weft : ≥ 1.0 kgf	ASTM D2261
Air Permeability	≥ 6.0	ASTM D737
Water Moisture Vapour Permeability	≥ 3000 g/m2 *24hr	ASTM E96-B
Finish	P/D	
Application	Recommend for clean room (Class 100), hoods, caps, socks, masks, shoes.	